

PATENT

Atty. Docket No.: 006915 USA P02/FEP/P3I/PJT
RW Ref. No.: APM/001-02-CP1-2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: :
Kenneth Collins, et al. :
 :
Entitled: PLASMA IMMERSION ION :
IMPLANTATION APPARATUS USING A : Group Art Unit: 2893
PLASMA SOURCE HAVING LOW :
DISSOCIATION AND LOW MINIMUM :
PLASMA VOLTAGE :
 : Examiner: Jack S. Chen
Serial No.: 10/646,533 :
 :
Filing Date: August 22, 2003 :

RESPONSE TO DOUBLE PATENTING REJECTION

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action (Double Patenting) dated April 1, 2009, applicants submit herewith a Terminal Disclaimer to overcome the double patenting rejection.

Although the claims have not been amended, a complete listing of claims is provided and begins on page 2.

Remarks begin on page 17 of this paper.